



科豐國際有限公司

Jandel 的針頭選擇應用參考

Type	Tip R	Force	Spacing	Typical Application
A	40u	100g	1 mm	金屬薄膜 Metal Film
B	100u	100g	1 mm	一般金屬 General Metal, 高離子摻雜 Hi dose implant
C	200u	100g	1 mm	中度離子摻雜 Medium dose implant [Rs = 1000ohm/sq]
D	500u	70g	1 mm	低離子摻雜 Low Dose implant.
				非常薄金屬薄膜 Very thin metal film such as TiN, ti, etc.
E	40u	200g	1.58mm	厚矽材 Thick substrate, 摻雜的矽晶片 dosed silicon wafers,
				擴散晶片 diffusion
F	40u	100g	0.635 mm	Similar to A probe for smaller [2mm]edge exclusion ,higher resolution measurement
G	100u	100g	0.635 mm	Similar to B probe for smaller [2mm]edge exclusion ,higher resolution measurement
H	200u	100g	0.635 mm	Similar to C probe for smaller [2mm]edge exclusion ,higher resolution measurement
FC	100u	100g	0.5mm	Similar to A probe for smaller[1.5mm]edge exclusion ,higher resolution measurement
GC	200u	100g	0.5mm	Similar to C probe for smaller[1.5mm]edge exclusion ,higher resolution measurement